

Form PTO-1449

**INFORMATION DISCLOSURE CITATION
IN AN APPLICATION**

(Use several sheets if necessary)

Docket Number
211843-00022Application Number
10/183,768 - 10/748,078Applicant
Thomas HorskyFiling Date
June 28, 2002 12/30/04Group Art Unit
288T 2821**U. S. PATENT DOCUMENTS**

EXAMINER INITIAL	DOCUMENT NUMBER								DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROP.
JV	6	4	5	2	3	3	8		9/17/02	Horsky	245	111.81	
JV	6	2	8	8	4	0	3		9/11/01	Horsky et al.	250	427	
JV	3	5	8	1	1	9	5		6/10/68	Robert L. Jepsen	324	470	
JV	5	5	4	3	6	2	5		8/6/96	Johnson et al.	250	427	
JV	6	3	5	2	6	2	6		3/5/02	von Zweck	204	298.04	
JV	4	7	4	0	6	9	8		4/26/88	Tamura et al.	250	310	
JV	4	2	1	7	8	5	5		8/19/80	Takagi	118	719	
JV	4	1	5	2	4	7	8		5/1/79	Takagi	428	221	
JV	3	5	5	7	3	6	5		12/22/67	Ralph Elliott Mayo Fairfield; Edward B. Delany, Ridgefield, Conn.	250	427	
JV	4	1	2	0	7	0	0		10/17/78	Morimoto	438	479	
JV	5	5	6	1	3	2	6		10/1/96	Ito et al.	257	751	
JV	5	6	8	6	7	8	9		11/11/97	Schoenbach et al.	313	491	
JV	5	5	2	8	0	3	4		6/18/96	Yamazaki et al.	250	309	
JV	4	9	4	3	7	1	8		07/90	Haines et al.	250	288	
JV	4	6	4	9	2	7	8		03/87	Chutjian et al.	250	423R	

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	Translation	
						Yes	No

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

JV	Thomas N. Horsky, Electron Beam Ion Source With Integral Low-Temperature Vaporizer, U.S. Patent Application Publication No. US 2002/0070672 A1 dated June 13, 2002
JV	Lo et al., Method and Apparatus for Multiple Charge particle Beams, U.S. Patent Application Publication No. US 2003/0001095 A1 dated January 2, 2003
JV	Brautti et al., "Trapped Ion Source", IEEE Journal 1998, pp. 2729-2731
JV	Boggia et al., "Study of a Trapped Ion Source", IEEE Journal, pp. 1433-1435

EXAMINER

DATE CONSIDERED 09/28/04

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.